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Endoh et al.

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(45) **Date of Patent:** **Nov. 7, 2006**

(54) **ELECTRONIC DEVICE HAVING SIDE ELECTRODE, METHOD OF MANUFACTURING THE SAME, AND APPARATUS USING THE SAME**

5,774,342 A * 6/1998 Brandenburg et al. 361/774
5,886,877 A * 3/1999 Shingai et al. 361/768
6,303,876 B1 * 10/2001 Miyazaki 174/260

FOREIGN PATENT DOCUMENTS

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JP 2002-252534 A 9/2002

* cited by examiner

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(57) **ABSTRACT**

(21) Appl. No.: **11/052,817**

A film having a recess provided in a surface of the film is provided. The recess included a first portion and a second portion connected with the first portion. The second portion is deeper than the first portion. The recess in the film is filled with a conductive paste so as to fill the first portion and the second portion of the recess with a first portion and a second portion of the conductive paste, respectively. Then, the surface of the film is attached onto a surface of a substrate. The conductive paste is transferred to the surface of the substrate by removing the film from the substrate so as to transfer the first portion and the second portion of the conductive paste to the surface of the substrate. The transferred first portion and the transferred second portion of the conductive paste are baked to provide a first portion and the second portion of a conductor pattern, respectively. An insulating layer is provided on the conductor pattern. Then, the substrate, the insulating layer, and the conductor pattern are cut along a first border extending across the second portion of the conductor pattern, thus providing an electronic device. In this method, the side electrode is formed simultaneously to the cutting of the substrate.

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Jan. 20, 2005 (JP) 2005-012300

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H05K 1/03 (2006.01)

(52) **U.S. Cl.** 174/255; 174/257; 174/260

(58) **Field of Classification Search** 174/255,
174/260, 261, 257, 256; 361/813

See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

5,248,854 A * 9/1993 Kudoh et al. 174/261

7 Claims, 18 Drawing Sheets

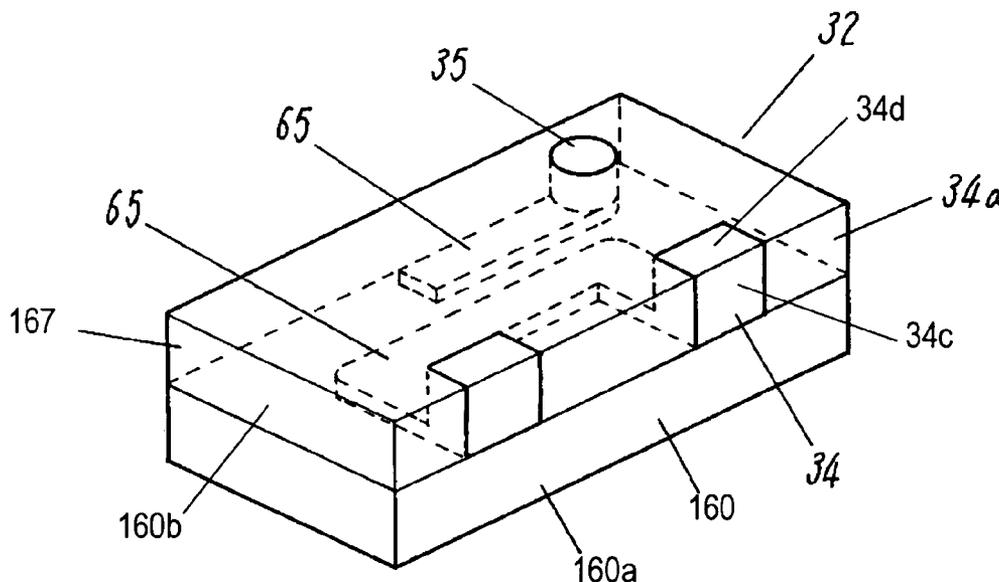


Fig. 1

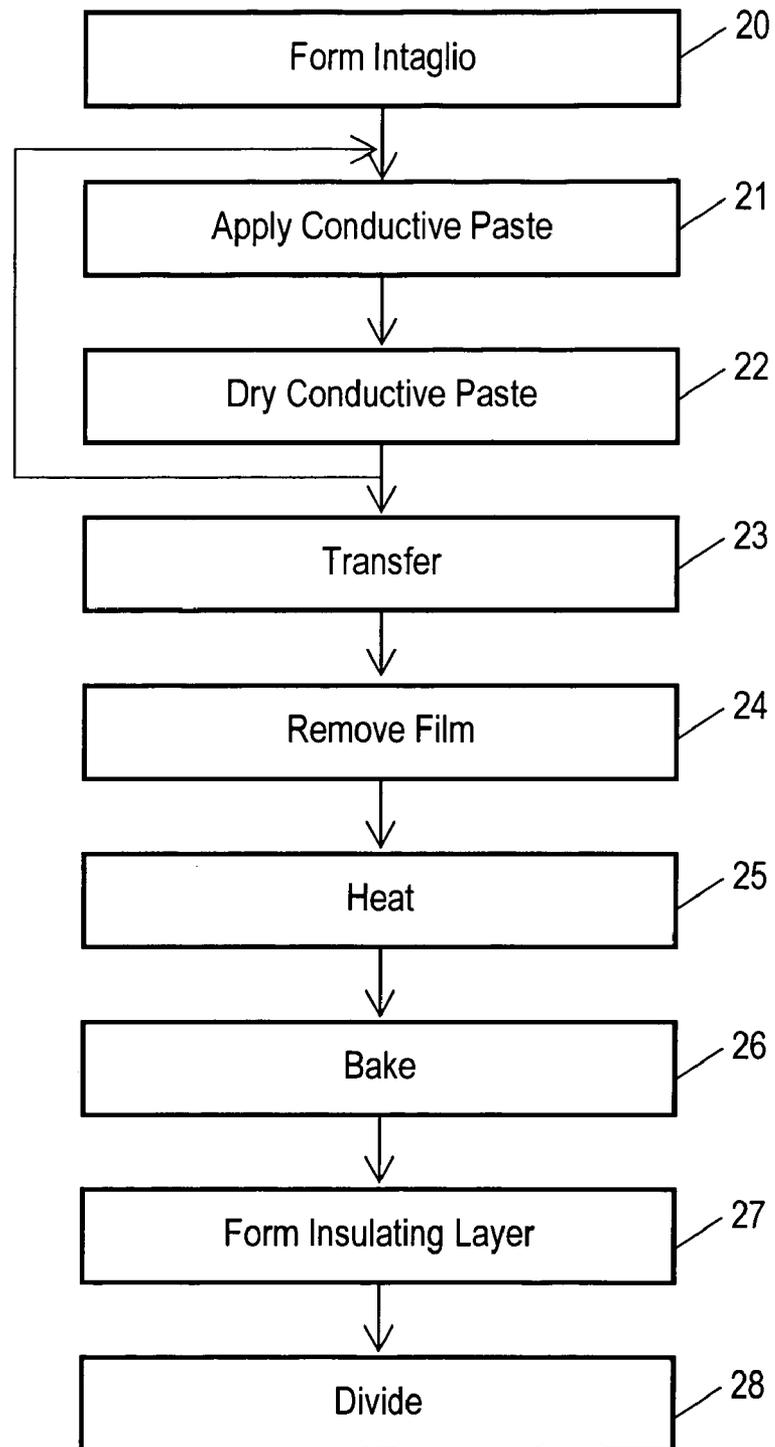


Fig. 2

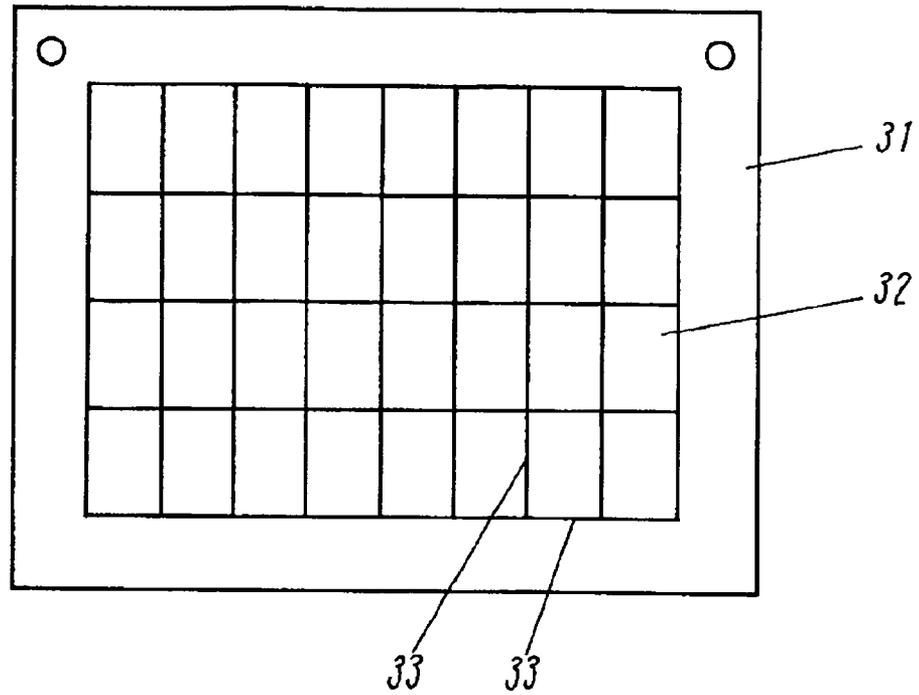


Fig. 3

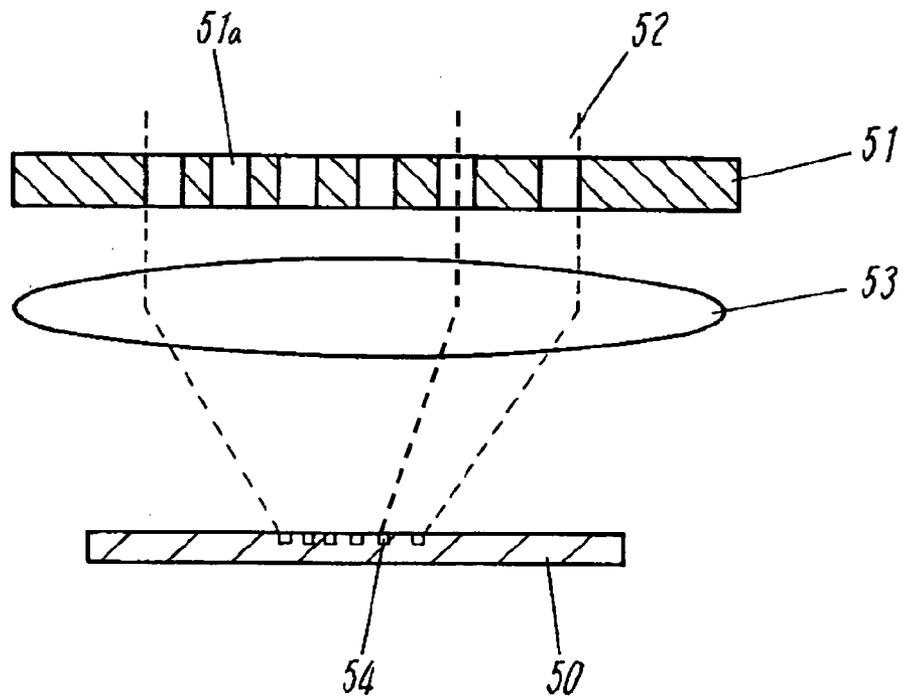


Fig. 4

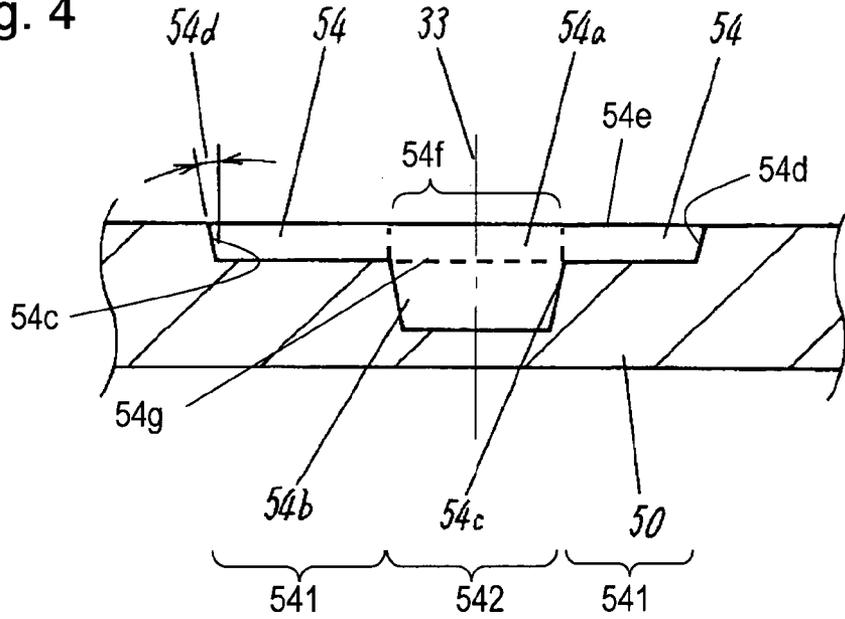


Fig. 5A

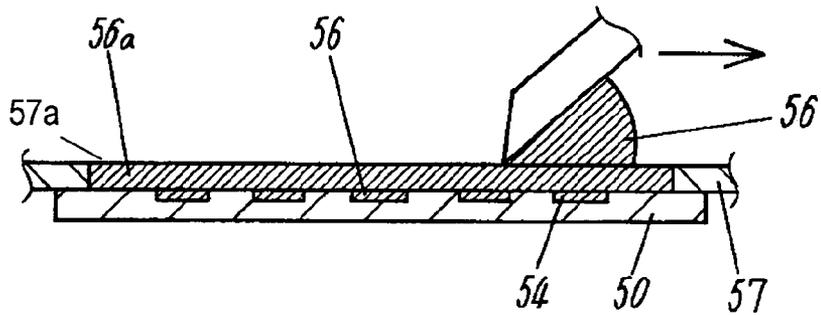


Fig. 5B

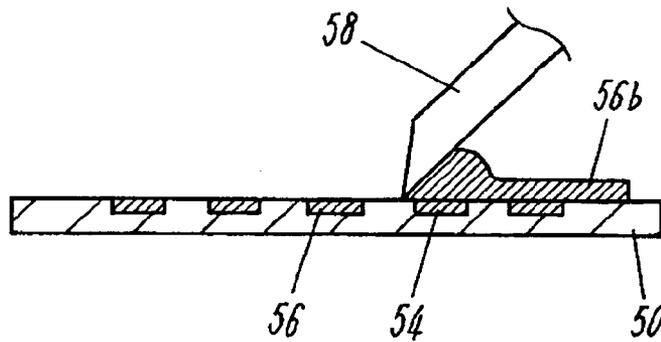
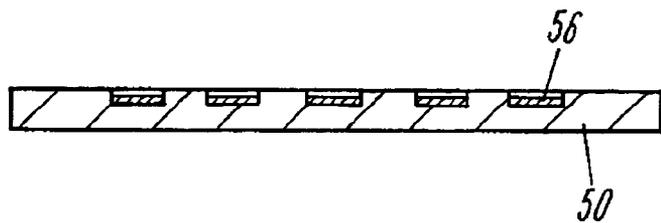


Fig. 5C



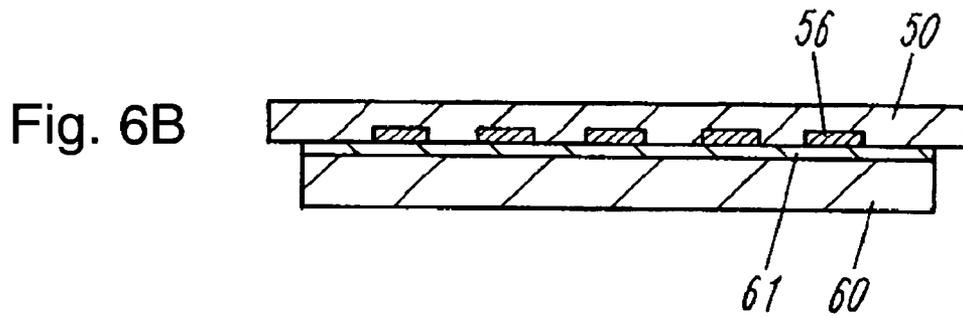
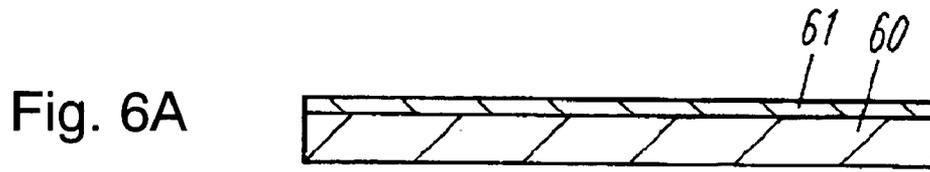


Fig. 7

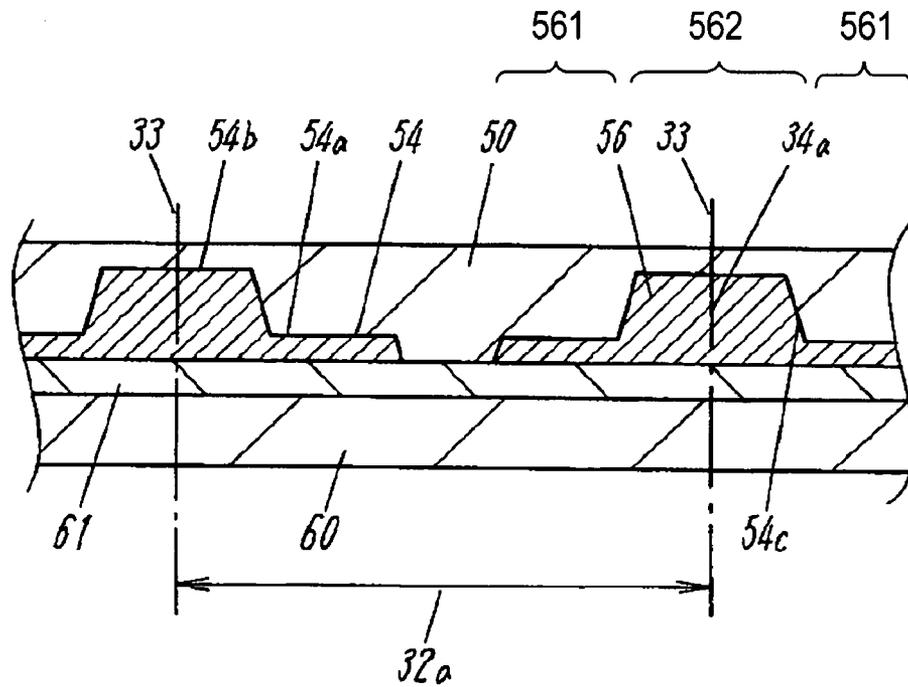


Fig. 8

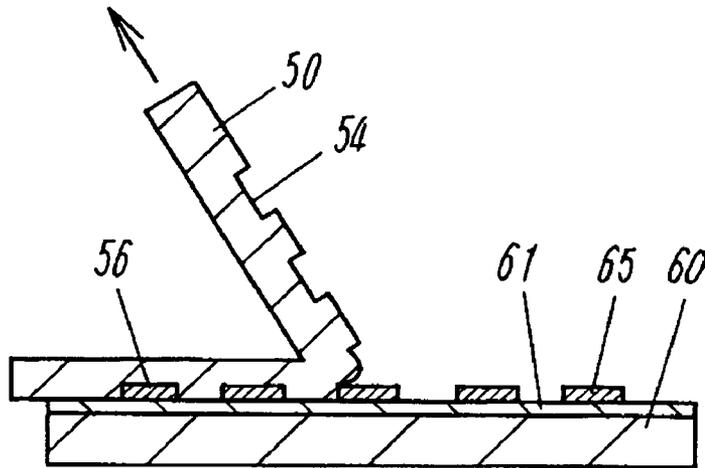
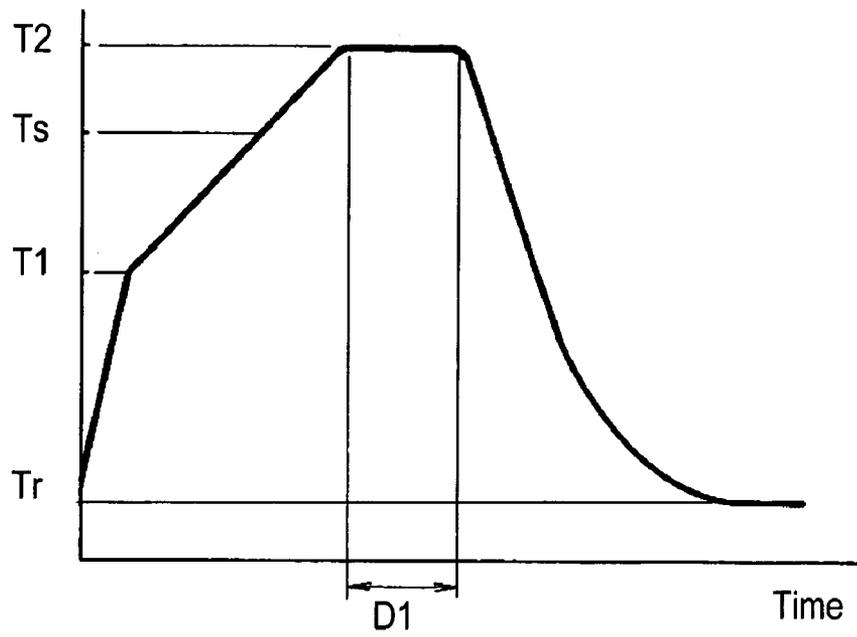


Fig. 9

Temperature



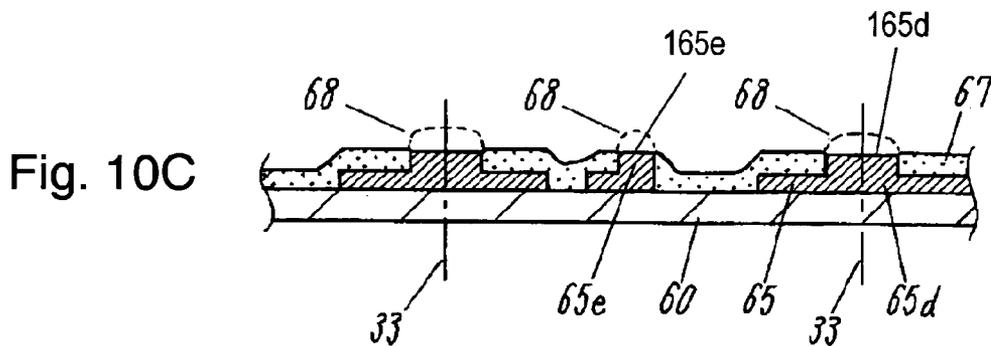
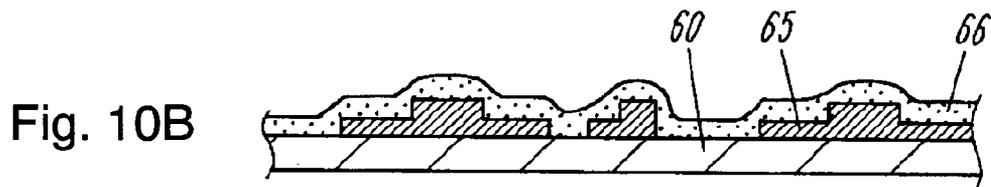
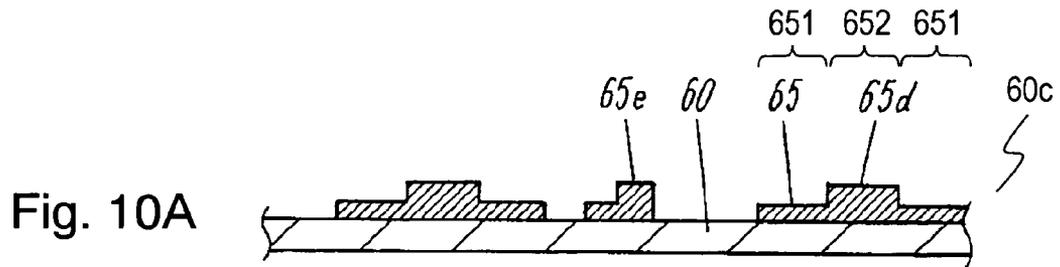


Fig. 11

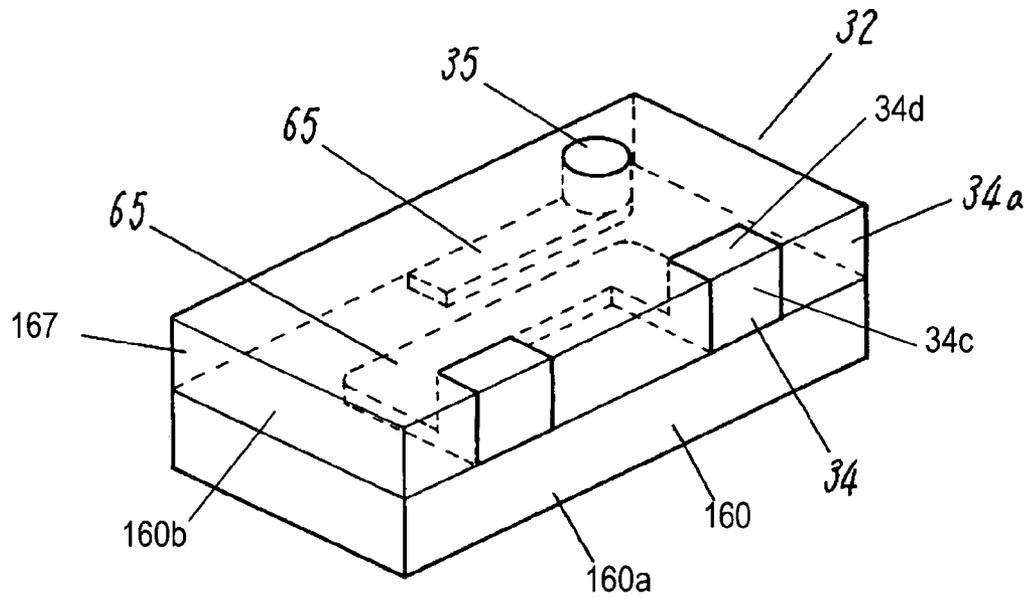


Fig. 12

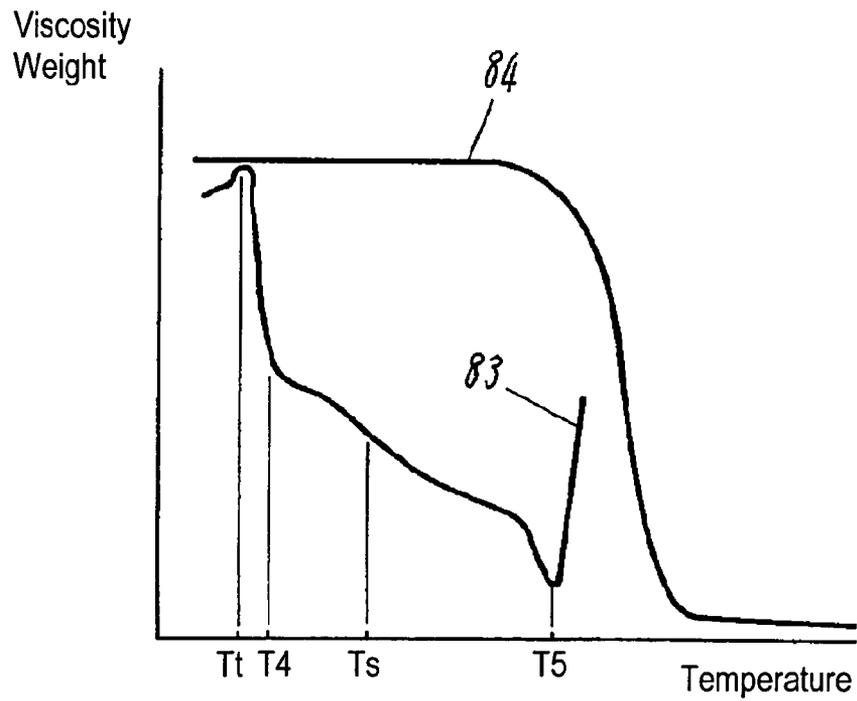


Fig. 13

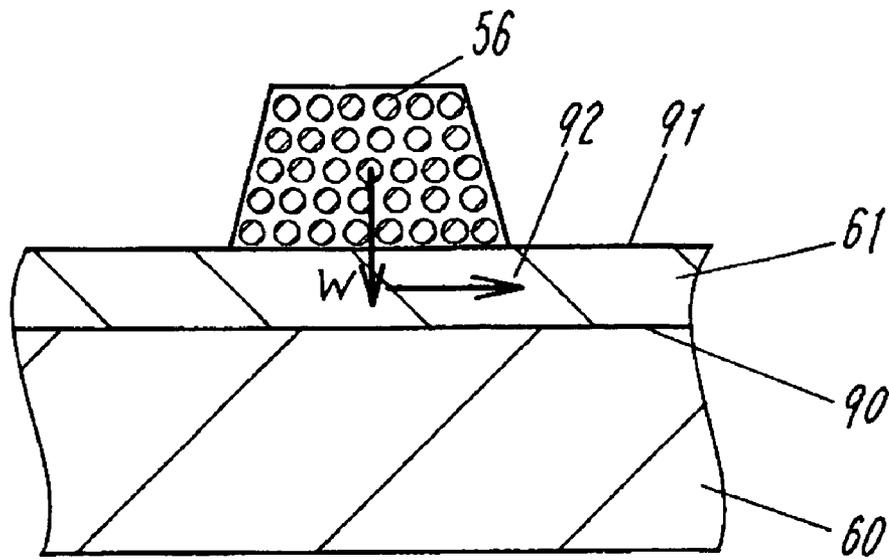


Fig. 14A

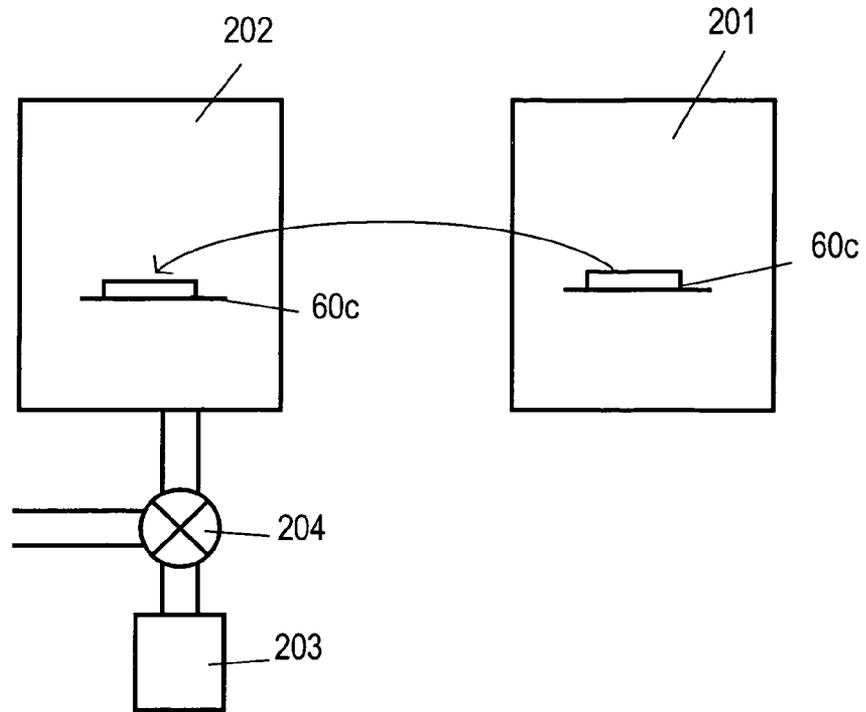


Fig. 14B

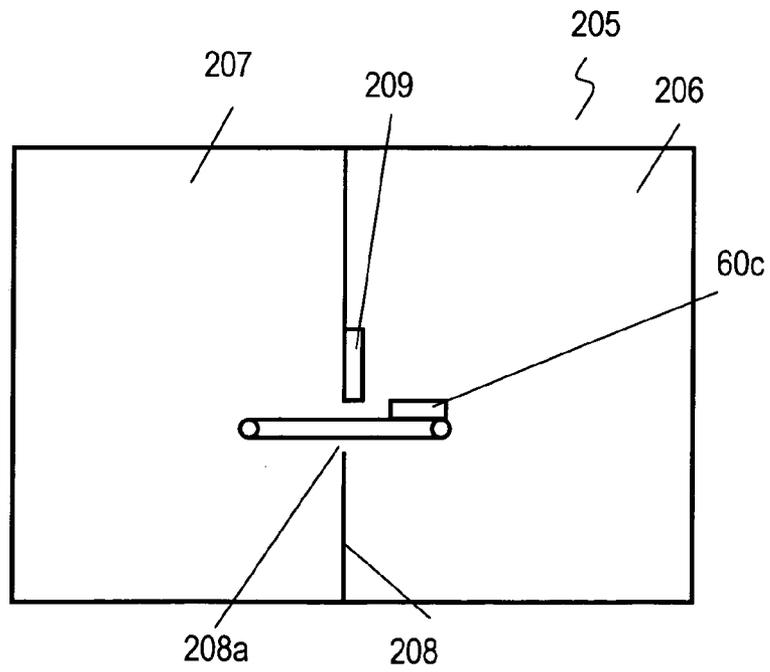


Fig. 15

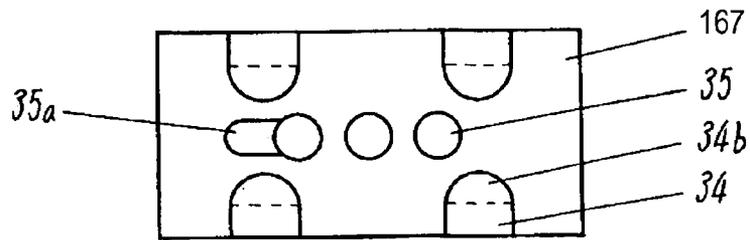


Fig. 16

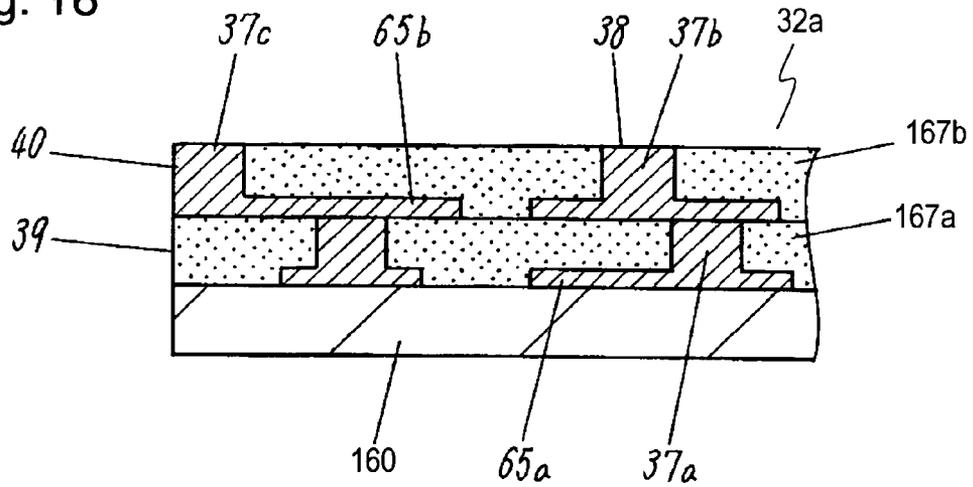


Fig. 17

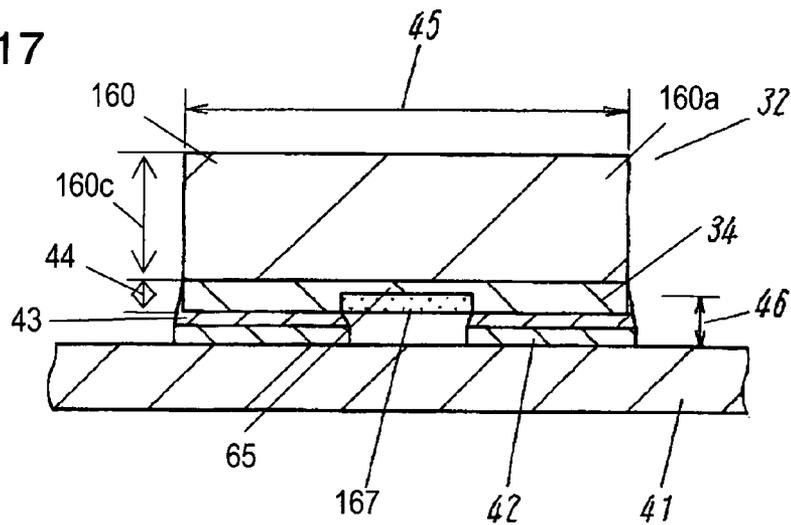


Fig. 18

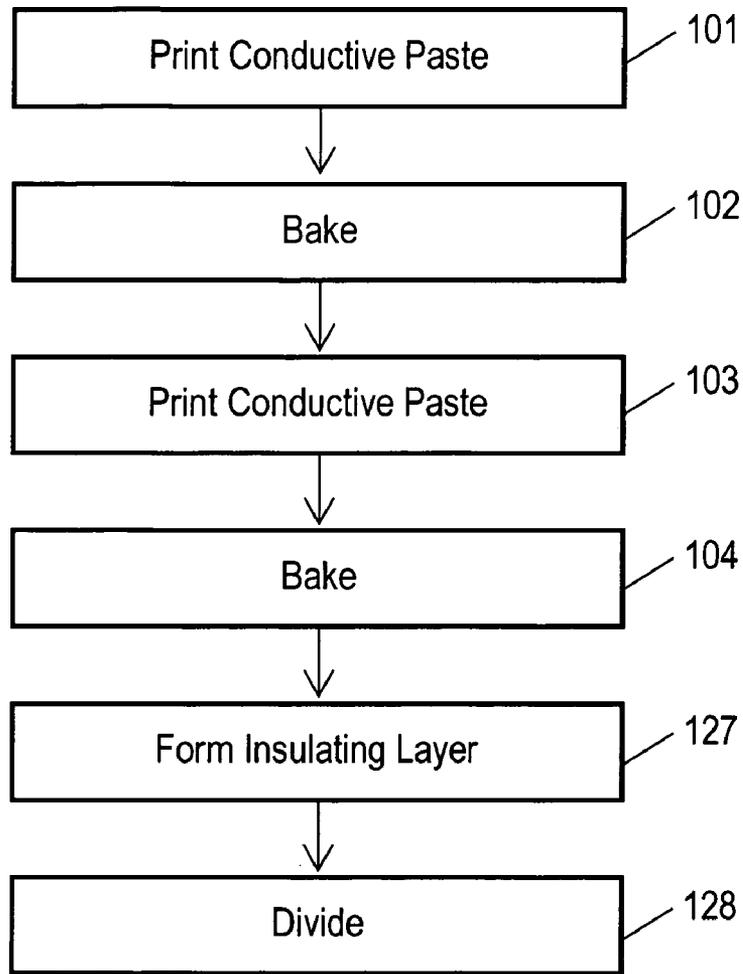


Fig. 19A

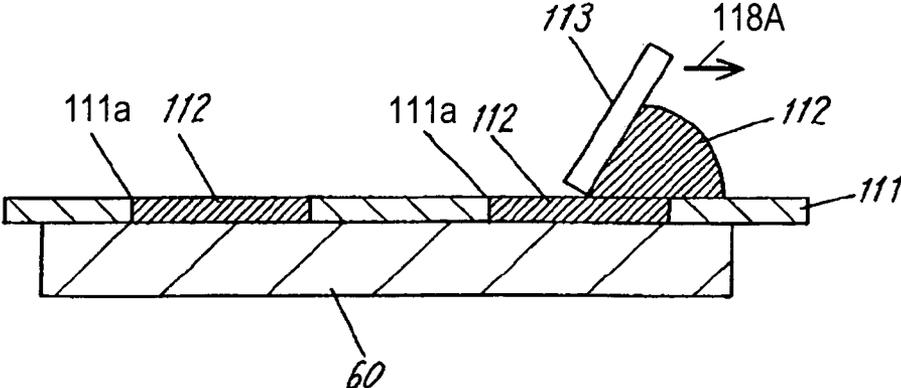


Fig. 19B

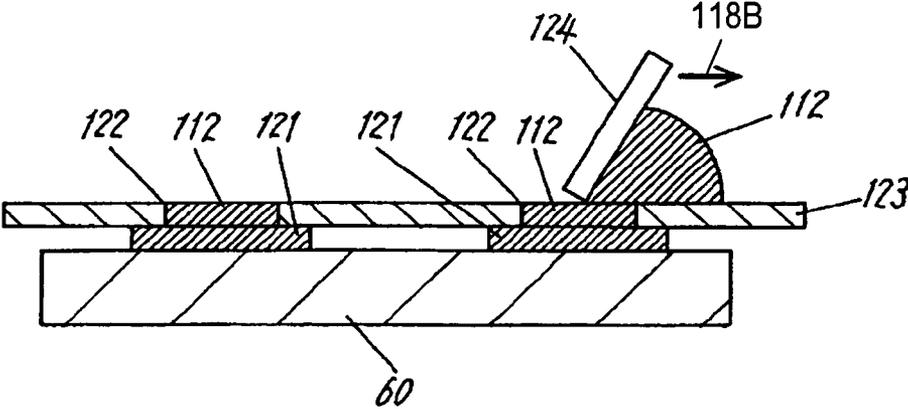


Fig. 19C

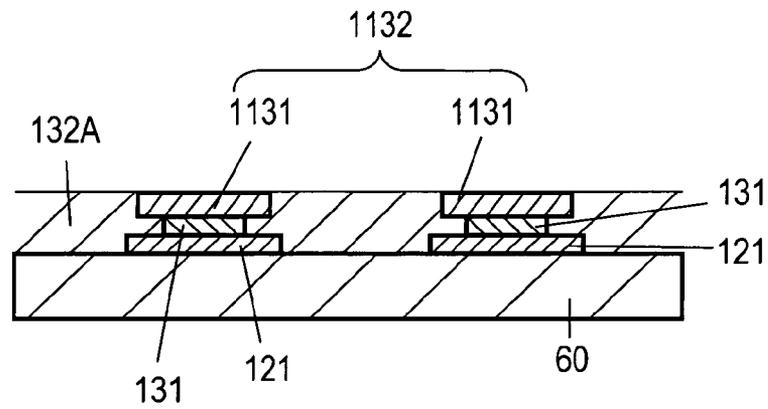


Fig. 19D

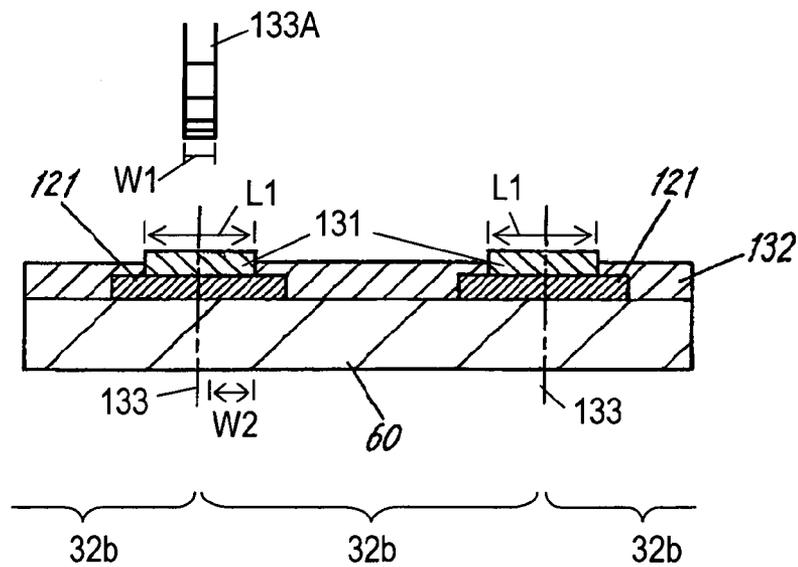


Fig. 20

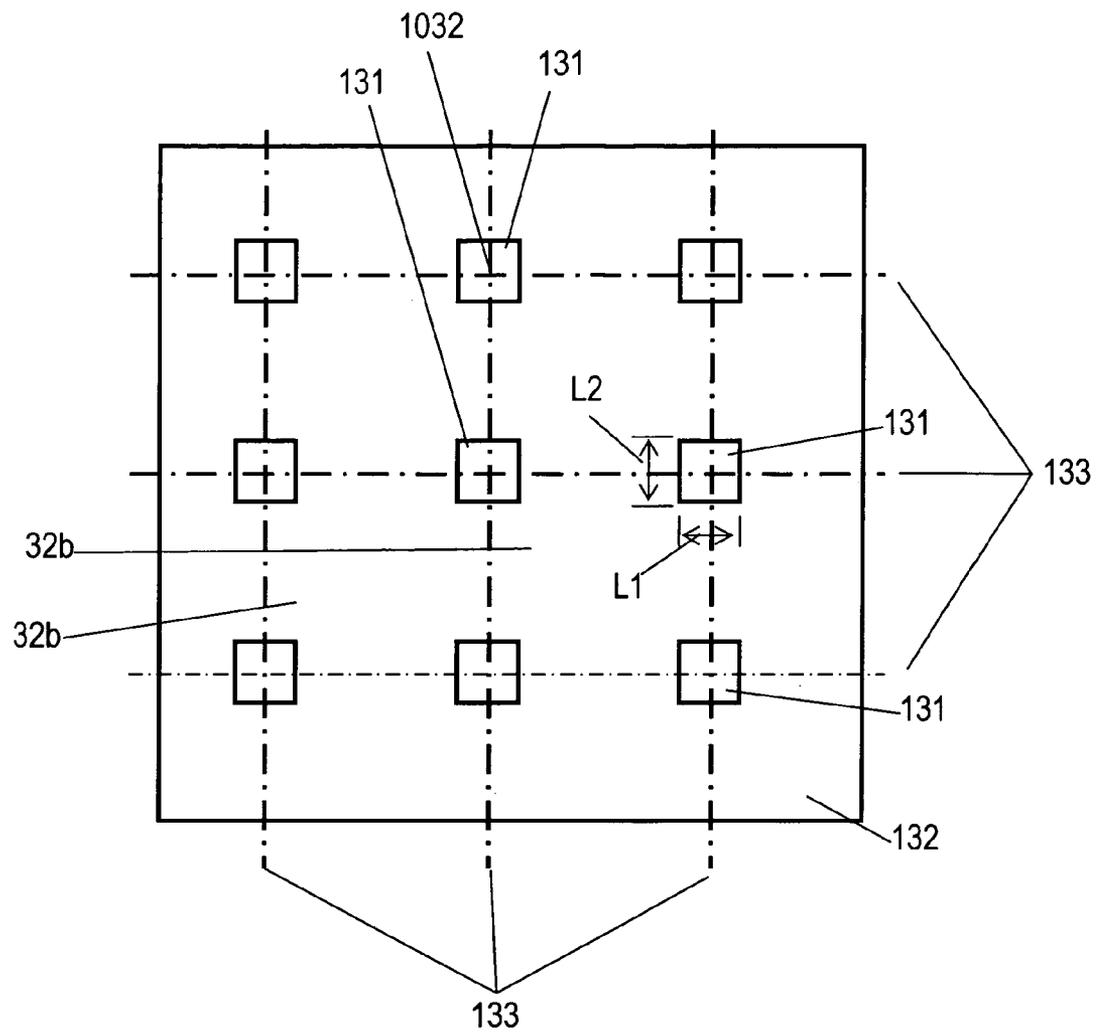


Fig. 21A

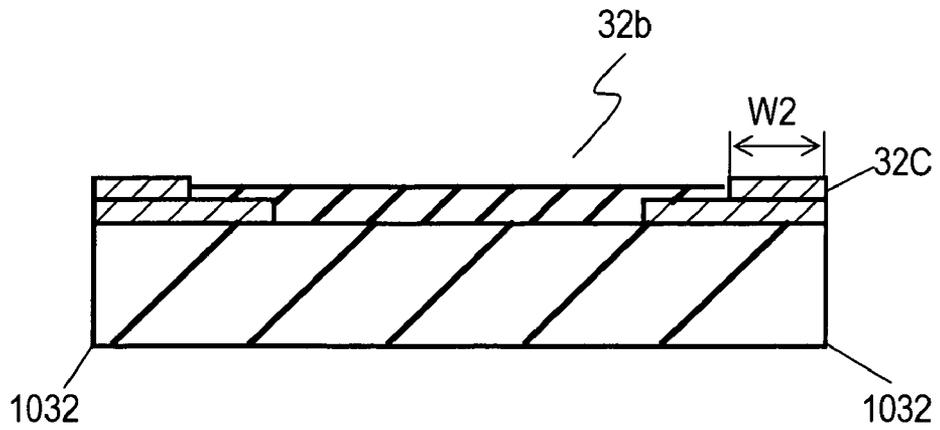


Fig. 21B

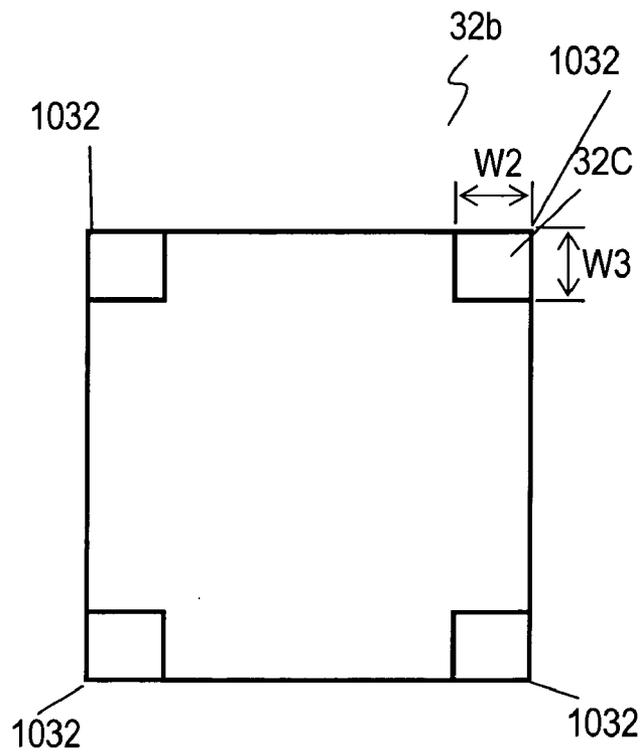


Fig. 22

Prior Art

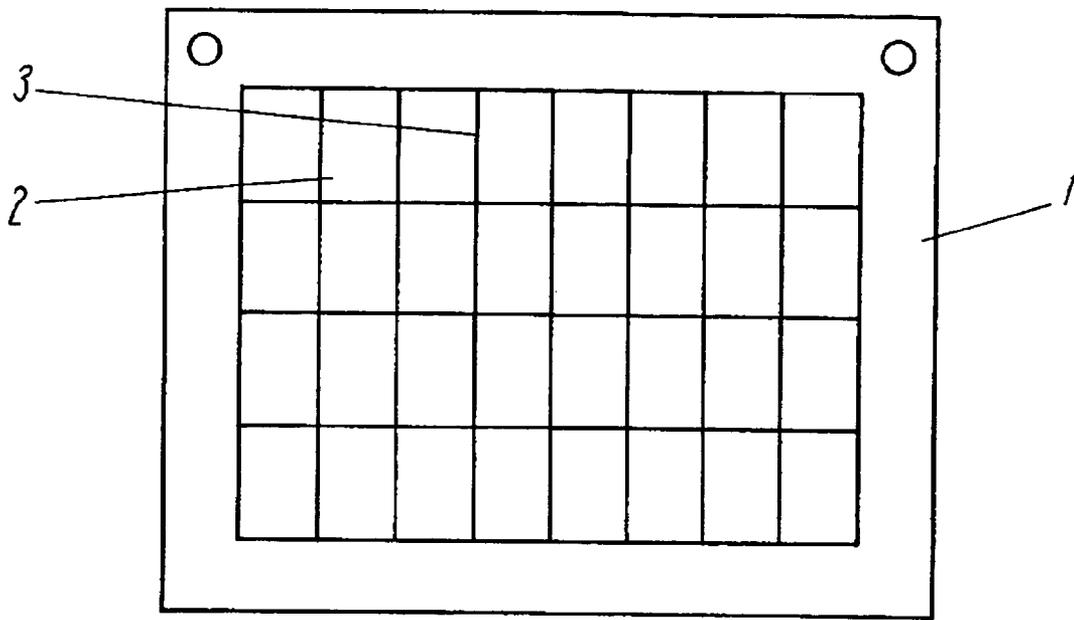


Fig. 23

Prior Art

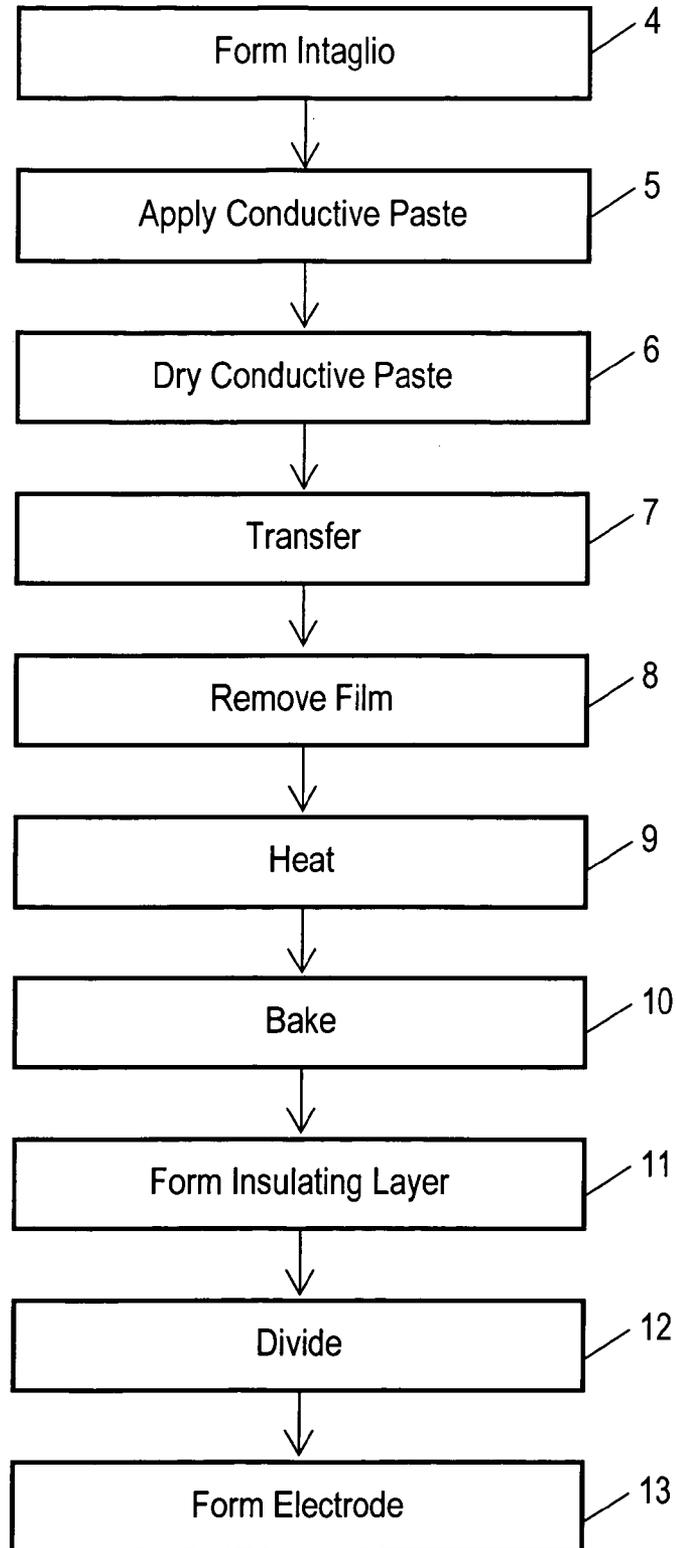
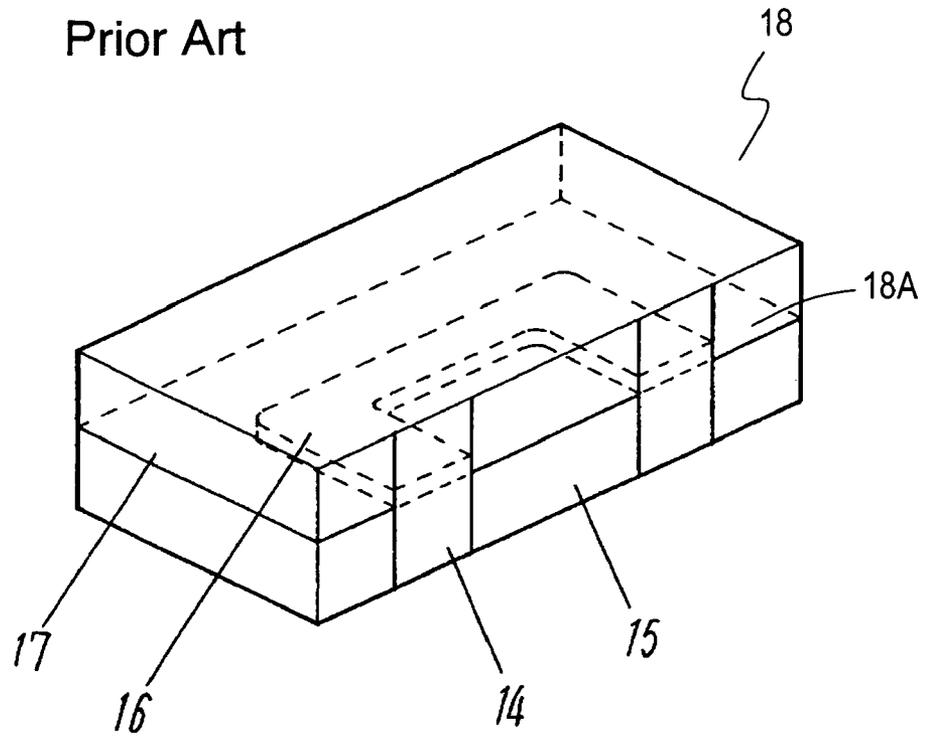


Fig. 24



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**ELECTRONIC DEVICE HAVING SIDE
ELECTRODE, METHOD OF
MANUFACTURING THE SAME, AND
APPARATUS USING THE SAME**

FIELD OF THE INVENTION

The present invention relates to an electronic device having a side electrode, a method of manufacturing the electronic device, and an apparatus using the electronic device.

BACKGROUND OF THE INVENTION

A surface-mount electronic device may be manufactured by the following processes. FIG. 22 illustrates the processes. A wiring pattern is provided on a substrate 1 having a sheet shape to provide chip substrates 2 arranged like a grid. The substrate 1 is divided along borders 3 into the chip substrates 2. Then, a side electrode is provided on a separated side, i.e., a side surface of the chip substrate 2, providing a surface-mount electronic device.

FIG. 23 illustrates a method of manufacturing the conventional surface-mount electronic device disclosed in Japanese Patent Laid-Open Publication No.2002-252534. A Recess is formed in a polyimide film with laser beam to provide an intaglio (Step 4). The recess in the film is filled with electrically-conductive paste by a squeegee (Step 5). The conductive paste filled at Step 5 is dried (Step 6). The film having the recess filled with the conductive paste is placed over a substrate 1 to transfer the conductive paste onto the substrate 1 (Step 7). The film is then removed from the substrate 1 (Step 8). The substrate 1 having the conductive paste transferred thereon is heated (Step 9) and baked at about 850° C. (Step 10). The baking at Step 10 has the conductive paste serve as a conductor pattern. An insulating layer is provided on the conductor pattern and the substrate 1 (Step 11). The substrate 1 having the insulating layer thereon is divided along borders 3 into chip substrates 2 (Step 12). A silver material is applied on a side of the chip substrate 2, providing a side electrode.

FIG. 24 is a perspective view of the conventional surface-mount electronic device 18 manufactured by the method shown in FIG. 23. Conductor pattern 16 is provided on substrate 15 corresponding to the chip substrate 2. An insulating layer 17 is provided on conductor pattern 16 and substrate 15. Conductor pattern 16 is connected to side electrode 14 provided on side 18A of electronic device 18.

SUMMARY OF THE INVENTION

A film having a recess provided in a surface of the film is provided. The recess included a first portion and a second portion connected with the first portion. The second portion is deeper than the first portion. The recess in the film is filled with a conductive paste so as to fill the first portion and the second portion of the recess with a first portion and a second portion of the conductive paste, respectively. Then, the surface of the film is attached onto a surface of a substrate. The conductive paste is transferred to the surface of the substrate by removing the film from the substrate so as to transfer the first portion and the second portion of the conductive paste to the surface of the substrate. The transferred first portion and the transferred second portion of the conductive paste are baked to provide a first portion and the second portion of a conductor pattern, respectively. An insulating layer is provided on the conductor pattern. Then,

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the substrate, the insulating layer, and the conductor pattern are cut along a first border extending across the second portion of the conductor pattern, thus providing an electronic device.

In this method, the side electrode is formed simultaneously to the cutting of the substrate.

BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 illustrates a method of manufacturing a surface-mount electronic device according to Exemplary Embodiment 1 of the present invention.

FIG. 2 is a plan view of a substrate for providing the electronic device according to Embodiment 1.

FIG. 3 illustrates a method of making an intaglio for manufacturing the electronic devices according to Embodiment 1.

FIG. 4 is a cross sectional view of a recess formed in the intaglio for manufacturing the electronic device according to Embodiment 1.

FIGS. 5A to 5C are cross sectional views of the electronic device for illustrating a method of manufacturing the device according to Embodiment 1.

FIGS. 6A and 6B are cross sectional views of the electronic device for illustrating the method for manufacturing the device according to Embodiment 1.

FIG. 7 is a cross sectional view of the electronic device for illustrating the method of manufacturing the device according to Embodiment 1.

FIG. 8 is a cross sectional view of the electronic device for illustrating the method of manufacturing the device according to Embodiment 1.

FIG. 9 is a temperature profile in the method of manufacturing the electronic device according to Embodiment 1.

FIGS. 10A to 10C are cross sectional views of the electronic device for illustrating the method of manufacturing the device according to Embodiment 1.

FIG. 11 is a perspective view of the electronic device according to Embodiment 1.

FIG. 12 illustrates characteristics of resin used in the method of manufacturing the electronic device according to Embodiment 1.

FIG. 13 is a cross sectional view of the electronic device for illustrating the method of manufacturing the device according to Embodiment 1.

FIGS. 14A and 14B are schematic views of apparatuses for manufacturing the electronic device according to Embodiment 1.

FIG. 15 is a plan view of a surface-mount electronic device according to Exemplary Embodiment 2 of the invention.

FIG. 16 is a cross sectional view of a surface-mount electronic device according to exemplary Embodiment 3 of the invention.

FIG. 17 is a cross sectional view of a surface-mount electronic device according to Exemplary Embodiment 4 of the invention.

FIG. 18 illustrates processes in a method of manufacturing a surface-mount electronic device according to Exemplary Embodiment 5 of the invention.

FIGS. 19A-19D are cross sectional views of the electronic device for illustrating the method of manufacturing the device according to Embodiment 5.

FIG. 20 is a top view of a substrate shown in FIG. 19D.

FIG. 21A is a cross sectional view of the electronic device according to embodiment 5.

FIG. 21B is a top view of the electronic device according to embodiment 5.

FIG. 22 is a plan view of a substrate for manufacturing a conventional surface-mount electronic device.

FIG. 23 illustrates processes for manufacturing the conventional electronic device.

FIG. 24 is a perspective view of the conventional electronic device.

DETAILED DESCRIPTION OF THE PREFERRED EMBODIMENTS

Exemplary Embodiment 1

FIG. 1 illustrates processes in a method of manufacturing a surface-mount electronic device according to Exemplary Embodiment 1 of the present invention. FIG. 2 is a plan view of a substrate to be provided with the electronic device of Embodiment 1. A recess is formed in a film by laser beam, providing an intaglio (Step 20). The recess in the film is filled with an electrically-conductive paste (Step 21). The conductive paste is dried (Step 22). The filling of the paste at Step 21 and the drying of the paste at Step 22 may be repeated a predetermined number of times. The film having the recess filled with the conductive paste is attached onto a substrate coated with an adhesive, and then, pressed while heated (Step 23). Then, the film is removed from the substrate, hence transferring the conductive paste on the substrate (Step 24). The substrate having the conductive paste thereon is heated (Step 25), and the conductive paste is baked (Step 26), providing an conductor pattern on the substrate. An insulating layer is formed on the conductor pattern and the substrate (Step 27). The substrate having the insulating layer thereon is divided into chip substrates along a border between the chip substrates by dicing (Step 28). As shown in FIG. 2, chip substrates 32 are formed in substrate 31 having a sheet shape. Substrate 31 is divided into chip substrates 32 along border 33 between chip substrates 32 at Step 28 shown in FIG. 1, providing the chip substrates 32 each serving as the surface-mount electronic device. The border 33 defines a side surface of chip substrate 32.

The processes shown in FIG. 1 of the method of manufacturing the electronic device according to Embodiment 1 will be described in more detail.

FIG. 3 illustrates a process for providing the recess in the film at Step 20 shown in FIG. 1. Film 50 is made of polyimide having a thickness of 125 μm . Chrome mask 50 is placed over film 50. Chrome mask 51 has aperture 51a formed therein. Lens 53 is positioned between chrome mask 51 and film 50. Excimer laser 52 is emitted from above to chrome mask 51. Excimer laser 52 runs through aperture 51a in mask 51 and lens 52, and forms recess 54 corresponding to aperture 51a in film 50.

FIG. 4 is a cross sectional view of recess 54. A side wall of recess 54 in film 50 flares at angle 54d ranging substantially from 2° to 6° toward opening 54e where recess 54 opens. This structure allows the conductive paste filled at Step 24 to be easily removed from the recess 54, hence providing the conductor pattern precisely.

Recess 54b is further provided at portion 54f of recess 54 at border 33. That is, recess 54a having a depth equal to that of recess 54 is formed at portion 54f of recess 54, and further, recess 54b is formed at bottom 54g of recess 54a. Recess 54a and recess 54b form electrode recess 54c. In other words, recess 54 includes shallow portion 541 and deep portion 542 deeper than portion 541 and connected with portion 541.

Walls of recesses 54, 54a, 54b, and 54c in film 50 may be coated with carbon fluoride material to provide molecular layer of the carbon fluoride material. This layer allows the conductive paste to be easily removed from recesses 54, 54a, 54b, and 54c and to provide the conductor pattern precisely.

FIGS. 5A to 5C are cross sectional views of film 50 having recess 54 filled with conductive paste at Step 21 shown in FIG. 1.

As shown in FIG. 5A, screen 57 having a thickness of 100 μm and having aperture 57a is placed on film 50. Conductive paste 56 is applied through aperture 57a onto film 50 by screen printing. Thereby, recess 54 in film 50 is filled with conductive paste 56, and layer 56a of conductive paste 56 having a thickness of about 100 μm is formed on film 50. Screen 57 is made of stainless steel. Aperture 57a has a size greater than the entire area provided with recess 54, and recess 54 is thoroughly filled with conductive paste 56. Film 50 is then spun with a centrifugal machine so that the conductive paste 56 distributes to the entire area of recess 54. The centrifugal machine eliminates tiny bubbles which may be developed in conductive paste 56 during the filling.

Then, as shown in FIG. 5B, unnecessary conductive paste 56a other than conductive paste 56 filling recess 54 is removed off from film 50 with squeegee 58.

Then, conductive paste 56 in recess 54 is dried at a temperature such that a solvent contained in conductive paste 56 evaporates but does not deteriorate (Step 22 shown in FIG. 1). The solvent in conductive paste 56 according to Embodiment 1 employs alcohol solvent, such as isopropyl alcohol. Conductive paste 56 includes mainly about 60 wt. % of silver powder, about 38 wt. % of the solvent, and about 2 wt. % of binder. Conductive paste 56 can be dried preferably at about 150° C.

After conductive paste 56 containing about 38 wt. % of the solvent is dried, the paste has a volume decreases by the volume of the solvent, as shown in FIG. 5C. For compensation, another conductive paste 56 is applied into the recess 56 (Step 21 shown in FIG. 1) and dried again (Step 22 in FIG. 1). The applying of the paste at Step 21 and the drying of the paste at Step 22 may be repeated several times (five times according to Embodiment 1) until the recess 54 is fully filled with conductive paste 56.

According to Embodiment 1, the concentration of the silver powder in conductive paste 56 is adjusted to about 60 wt. % for easily printing the paste. The more the concentration of the silver powder, the less the number of the operations at Steps 21 and 22 may be repeated.

FIGS. 6A and 6B are cross sectional views of film 50 having recess 50 filled with dried conductive paste 56 and placed upside down on substrate 60.

As shown in FIG. 6A, substrate 60 is made of alumina and has a surface coated with adhesive layer 61 made of thermoset adhesive, such as polyvinyl butylal (PVB) resin. For example, substrate 60 is immersed into mixture liquid of acetone and toluene including the PVB resin dissolving therein. Substrate 60 is dried and has adhesive layer 61 deposited thereon. The mixture liquid containing acetone, toluene, and the PVB resin can naturally be dried at a room temperature.

Then, as shown in FIG. 6B, film 50 having recess 54 filled with conductive paste 56 onto adhesive layer 61 on alumina substrate 60. The alumina substrate 60 with film 50 is placed between rubber plates (not shown) to be pressed by the plates during heated. The heating causes the adhesive layer

61 to melt and penetrate into conductive paste **56** in recess **54**, so that the PVB resin in adhesive layer **61** is mixed with conductive paste **56**.

The heating is executed at a temperature higher than a glass transition temperature for preventing film **50** from separating from the alumina substrate **60** around adhesive layer **61**. The temperature for the heating is lower than a temperature at which the degree of polymerization of the PVB resin becomes zero in order to prevent voids on adhesive layer **61**. The voids may be gas, such as steam generated by fluctuation of molecular bonding in the PVB resin. There is no way to allow gas generated in recess **54** to leak, and the gas remain in conductive paste **56**.

After adhesive layer **61** containing the PVB resin is heated at 175° C. in an atmosphere for about twenty minutes, the degree of polymerization of the PVB resin becomes zero. The temperature for the heating according to Embodiment 1 is low, 140° C., since the fluctuation of the molecular bonding in the PVB resin steadily proceeds and generates undesired gas even at a temperature lower than 175° C. This process provides the conductor pattern precisely with no defect in its shape.

Conductive paste **56** on adhesive layer **61** is cooled and cured, and is accordingly bonded to substrate **60** securely. The cooling is executed until the temperature of the adhesive layer **61** becomes lower than the glass transition temperature. If the temperature remains not lower than the glass transition temperature, the PVB resin in adhesive layer **61** may not be cured completely. When film **50** is transported, the film may be separated from substrate **60**.

FIG. 7 is a cross sectional view of film **50** filled with conductive paste **56** and attached onto substrate **60** between two borders **33** adjacent to each other. Area **32a** between borders **33** corresponds to chip substrate **32** divided at Step **28** in FIG. 1. Electrode recess **54c** including recesses **54a** and **54b** is formed at a position corresponding to side surface **34a** of chip substrate **32**. Electrode recess **54c** is filled with conductive paste **56**. Electrode recess **54c** is portion **542** of recess **54** shown in FIG. 4. Border **33** extends across electrode recess **54c**, portion **542**. Conductive paste **56** includes portions **561** and **562** corresponding to portions **541** and **542** of recess **54**, respectively. Portion **542** of conductive paste **56** filling electrode recess **54c** is exposed when substrate **60** is divided along border **33** at Step **28**, thus serving as side electrode **34** of chip substrate **32**. That is, side electrode **34** is formed simultaneously to the dividing of substrate **60** into chip substrates **32**. Thus, a process of forming a side electrode of a conventional surface-mount electronic device at Step **13** shown in FIG. 23 is eliminated.

FIG. 8 is a cross sectional view of substrate **60** having film **50** removed off from substrate **60** at Step **24** shown in FIG. 1. As film **50** is removed from substrate **60**, conductive paste **56** in recess **54** is left as electrical conductor pattern **65** on substrate **60**. Conductor pattern **65** corresponding to aperture **51a** of chrome mask **51** is transferred on substrate **60**.

Then, conductive paste **56** on substrate **60** is heated at Step **25** shown in FIG. 1. FIG. 9 illustrates a temperature profile during the heating in which the vertical axis represents a temperature and the horizontal axis represents time. The heating at Step **25** shown in FIG. 1 is executed until the degree of polymerization of the PVB resin in adhesive layer **61** becomes about zero. As the PVB resin is further heated, decomposition of the resin is accelerated. Oxygen and hydrogen are accordingly removed as gas, such as steam, from the PVB resin in adhesive layer **61**, having carbon molecules remain in the resin. This reaction changes the color of adhesive layer **61** into brown, hardens layer **61**, and

reduces the weight of layer **61**. When the PVB resin in adhesive layer **61** is heated at 175° C. in atmosphere for substantially twenty minutes, the degree of polymerization in the resin becomes zero.

A temperature rise during the heating is preferably small from about 61° C., the glass transition temperature of the PVB resin, until the degree of polymerization of the resin becomes zero. The temperature rise during the heating of the PVB resin is determined to be small particularly near softening temperature T_s (147° C.) of the PVB resin.

According to Embodiment 1, substrate **60** is heated from room temperature T_r to temperature T_1 at a rate of 16° C./min, and then, the rate is decreased. When the temperature of substrate **60** reaches temperature T_2 , the rate is further decreased to about zero, and the substrate **60** is heated for duration D_1 . According to Embodiment 1, temperature T_1 is about 95° C. while temperature T_2 is about 175° C. Duration D_1 is about 25 minutes. While substrate **60** is heated at temperature T_2 for duration D_1 , the polymerizing degree of the PVB resin decreases to zero and decomposes rapidly.

According to the temperature profile shown in FIG. 9, the maximum temperature is temperature T_2 , about 175° C. Conductive paste **56** may contain copper powder instead of silver powder, while the copper powder is hardly oxidized at the maximum temperature. Substrate **60** having conductive paste **56** of copper powder transferred thereon is heated in the common atmosphere at Step **25**, and therefore, it is not necessary to heat substrate **60** in expensive inactive gas atmosphere, such as nitrogen atmosphere, thus allowing the surface-mount electronic devices to be manufactured inexpensively.

The baking at Step **26** shown in FIG. 1 will be described. The baking sinters the silver powder of conductive paste **56** on substrate **60** at a temperature of about 850° C. after substrate **60** is heated at Step **25**. The PVB resin in adhesive layer **61** is incinerated to carbon and water (steam) at a temperature of about 400° C. Accordingly, conductive paste **56** is securely fixed on alumina substrate **60** due to anchoring effect, thus providing the substrate with conductor pattern **65** thereon.

FIGS. 10A to 10C illustrate processes for forming the insulating layer at Step **27** shown in FIG. 1 for electrical and physical protection for conductor pattern **65** and substrate **60**.

FIG. 10A is a cross sectional view of wafer **60c** provided at Step **26** which includes substrate **60** and conductor patterns **65**, **65e**, and **65d** on substrate **60**. Conductor patterns **65d** and **65e** are provided by baking conductive paste **56** filled in electrode recesses **54c** shown in FIG. 7. Conductor pattern **65** have portions **651** and **652** corresponding to portions **561** and **562** of conductive paste **56**, respectively. Portion **652** of conductor pattern **65** is higher than portion **651** and is connected to portion **651**.

Then, insulating paste, such as crystalline glass, is applied on upper surfaces of conductor patterns **65**, **65d**, and **65e** and substrate **60**, as shown in FIG. 10B. The insulating paste is then baked, thus providing insulator **66** of crystalline glass on substrate **60**.

Then, insulator of insulator **66** on conductor patterns **65**, **65d**, and **65e** is ground to allow upper surfaces **165d** and **165e** of conductor patterns **65d** and **65e** to expose, providing insulating layer **67**. The insulating material of insulating layer **67** is not limited to glass and may be resin.

Then, substrate **60** having conductor patterns **65**, **65d**, and **65e** and insulating layer **67** thereon is cut along border **33** at Step **28** shown in FIG. **1**, dividing the substrate to provide chip substrates **32**.

FIG. **11** is a perspective view of chip substrate **32**, i.e., the surface-mount electronic device according to Embodiment 1. Chip substrate **32** includes substrate **160** and insulating layer **167** provided by dividing substrate **60** and insulating layer **67**, respectively. Substrate **60** is cut at Step **28** shown in FIG. **1**, and side surface **34c** of side electrode **34** corresponding to a cut surface of conductor pattern **65d** exposes. That is, side electrode **34** on side surface **34c** is flush with side surface **160a** of substrate **160** on the same plane. Conductor pattern **65d** provides side electrode **34**, and simultaneously to this, upper surface **34d** of side electrode **34** is provided. Conductor pattern **65e** provides upper electrode **35**.

Since being formed by offset printing, an edge shape of conductor pattern **65** is more uniform, less varies, and is more stable than that of a pattern formed by etching. This allows conductor pattern **65** to provide an inductor having a stable, constant inductance, hence providing a high-frequency circuit having a high performance.

Conductor pattern **65** is led to side surface **34a** of insulating layer **167** to provide side electrode **34** unitarily with conductor pattern **65**. Side surface **34a** of insulating layer **167** is flush with side surface **160a** of substrate **160**, and consequently, side electrode **34** exposes on the same plane as side surface **160a** of substrate **160** and side surface **34a** of insulating layer **167**. Since side electrode **34** is provided unitarily with conductor pattern **65**, a connection resistance between them is small. Further, since no process for forming the side electrode, the surface-mount electronic device is manufactured inexpensively.

Upper electrode **35** extends unitarily from conductor pattern **65** perpendicularly to upper surface **160b** of substrate **160** having conductor pattern **65** provided thereon in chip substrate **32**. Upper electrode **35** may be used as a ball grid array (BGA) terminal of a semiconductor device.

Side electrode **34** and upper electrode **35** are coated by nickel-tin alloy plating. Each of side electrode **34** and upper electrode **35** has a size of length of about 300 μm and a width of 60 μm .

Upper electrode **35** is formed unitarily with conductor pattern **65**, similarly to side electrode **34**, and hence, a connection resistance between them is small. The unitary forming eliminates an extra process for forming the upper electrode, thus allowing an inexpensive surface-mount electronic device.

Since side electrode **34** is not provided on side surface **160a** of substrate **160**, side surface **160a** of substrate **60** is insulated.

An effect of suppressing deformation of conductive paste **56** deflected during the heating at Step **25** in the processes of manufacturing the surface-mount electronic device shown in FIG. **1** according to Embodiment 1 will be described.

FIG. **12** illustrates the relationship between the temperature of the PVB resin in adhesive layer **61** and viscosity **83** of the resin and between the temperature and weight **84** of the resin. The horizontal axis represents the temperature and the vertical axis represents the viscosity and the weight.

Viscosity **83** of the PVB resin will be first explained. The PVB resin is heated from the room temperature to glass transition temperature T_t at Step **25**, thereby having the viscosity of the resin decreasing. When the temperature rises to about temperature T_4 , the viscosity sharply decreases.

When the temperature is temperature T_5 , the degree of polymerization of the PVB resin becomes zero, hence minimizing the viscosity. Then, the resin is heated at a temperature higher than temperature T_5 , the viscosity of the PVB resin increases. At temperature T_5 , most of the molecules of the PVB resin in the adhesive layer **61** remain as monomers. The PVB resin is heated at a temperature higher than temperature T_5 , thereby facilitating the decomposition of the PVB resin. The PVB resin accordingly decomposes into carbon molecules and gas, such as steam, and have the viscosity thereof increase.

Then, weight **84** of the PVB resin in adhesive layer **61** will be explained. At a temperature higher than temperature T_5 , hydrogen and oxygen in the PVB resin change into gaseous form, thereby decreasing weight **84** of the PVB resin sharply. If the heating at Step **25** is executed in the common atmosphere **25**, its decomposition is facilitated by hydrogen and oxygen in the resin and oxygen in air. Temperature T_5 is lower than a temperature for facilitating the decomposition in low-oxygen atmosphere, such as nitrogen atmosphere. That is, according to Embodiment 1, since substrate **60** is heated at Step **25** in the common atmosphere, the heating does not require expensive gas, such as nitrogen, and may be executed at low temperature 175° C., thus reducing energy to manufacture the electronic device.

FIG. **13** is a cross sectional view of substrate **60** at a temperature close to softening temperature T_s of the PVB resin shown in FIG. **12**. Adhesive layer **61** of the PVB resin is heated, the resin expands in proportion to its temperature. When the temperature is raised to near softening temperature T_s , the PVB resin in adhesive layer **61** becomes liquid having a viscosity. Then, the PVB resin flows outward from substrate **60** in direction **92** due to thermal expansion. At this moment, the moving speed of the PVB resin is about zero at interface **90** between adhesive layer **61** and substrate **60**, and increases as departing from interface **90**. The moving speed becomes maximum at upper surface **91** of adhesive layer **61**. Conductive paste **56** is located on the moving PVB resin in adhesive layer **61**, thereby receiving a frictional force at the interface between adhesive layer **61** and paste **56**. If the weight W of conductive paste **56** is small, the frictional force moves conductive paste **56** in direction **92**. That is, a portion of conductive paste **56** which has small weight W , i.e., which has a small cross section, moves more. A thin portion of conductive paste **56** moves more than a thick portion of paste **56** thicker than the thin portion, conductor pattern **65** deforms after the heating and baking due to a difference between respective moving distances of the thin and thick portions.

The viscosity of the PVB resin sharply decreases at a temperature higher than the glass transition temperature T_s . The degree of polymerization of the PVB resin is minimum at a temperature near temperature T_5 . Therefore, in the heating at Step **25** according to Embodiment 1, the increase from temperature T_s to temperature T_5 is reduced as much as possible.

The above operation reduces an expanding amount per time of adhesive layer **61**, thereby reducing the moving speed of the PVB resin. The movement of conductive paste **56** is accordingly reduced, thus reducing the deformation of conductor pattern **65** and providing pattern **65** accurately.

Upon being heated to a temperature higher than temperature T_5 , the PVB resin in adhesive layer **61** has its molecular structure broken, and the broken structure does not recover to the original structure even upon being cooled down. That is, after degree of polymerization of the PVB resin becomes zero, and then the PVB resin is cooled, the viscosity of the

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fills aperture **111a** in screen **111** with conductive paste **112**. Then, screen **111** is removed, and conductive paste **112** having a predetermined shape is applied and printed on substrate **60** (Step **101**). Conductive paste **112** provided at Step **101** is then baked (Step **102**), providing conductor pattern **121** (FIG. **19B**).

Then, screen **123** having aperture **122** smaller than aperture **111a** of screen **111** is placed on conductor pattern **121**, as shown in FIG. **19B**. Aperture **122** is located on conductor pattern **121**. conductive paste **112** is applied onto screen **123** and spread over with squeegee **124** moving in direction **118B** on a surface of the screen **123**. This operation fills aperture **122** in screen **123** with conductive paste **112**. Then, screen **123** is removed, and conductive paste **112** is applied and printed on conductor pattern **121** so that conductor pattern **121** exposes (Step **103**). Conductive paste **112** printed on conductor pattern **121** is then baked (Step **104**), providing conductor pattern **131** (FIG. **19C**). Screen **123** of Embodiment **5** has a thickness of about $40\ \mu\text{m}$, and conductor pattern **131** has a thickness of about $20\ \mu\text{m}$ after the baking.

Then, mask **1132** having masking regions **1131** larger than conductor pattern **131** and smaller than conductor pattern **121** is placed on conductor pattern **131**, as shown in FIG. **19C**. Then, insulating paste **132A** is applied through screen **1132**. Insulating paste **132A** is then baked and cured, providing insulating layer **132** on substrate **60** (Step **127**), as shown in FIG. **19D**. Insulating layer **132** is not provided on conductor pattern **131**. That is, a surface of insulating layer **132** is lower than a surface of conductor pattern **131**.

FIG. **20** is a top view of substrate **60** shown in FIG. **19D**. Conductor pattern **131** exposing from insulating layer **132** has a rectangular shape having length **L1** of $0.6\ \text{mm}$ and width **L2** of $0.5\ \text{mm}$.

Substrate **60** is then separated divided along border **133** extending across conductor pattern **131** (Step **128**), and provides surface mount-electronic devices **32b** shown in FIGS. **21A** and **21B**. Border **133** extends across substantially the center of conductor pattern **131**. Substrate **60** is divided at Step **128** with rotary cutting blade **133A** having a thickness **W1** of about $0.2\ \text{mm}$. Cutting blade **133A** accordingly provides a cutting loss of $0.2\ \text{mm}$, providing surface mount electronic device **32b** having electrode **32c** at each corner **1032** of the device. Electrode **32c** has four-sided shape having length **W3** of about $0.15\ \text{mm}$ and width **W2** of about $0.2\ \text{mm}$ viewed from an upper viewpoint.

As above, the dividing at Step **128** provides side electrode **32c**, and make another process of forming side electrode **32c** unnecessary, providing inexpensive surface mount electronic device **32b**.

Conductor pattern **131** to become side electrode **32c** is provided by printing with screen **123**, and thus is precisely shaped to have a size of length **L1** of $0.6\ \text{mm}$ and width **L2** of $0.5\ \text{mm}$. This size allows side electrode **32c** of surface mount-electronic device **32b** to be soldered at a large area onto a mother board, thus increasing bonding strength between device **32b** and the mother board.

Applying of conductive paste **112** at Steps **101** and **103** with screens **111** and **123**, respectively, may be repeated to thicken conductor patterns **121** and **131**. This operation simplifies the processes, thus providing further inexpensive surface mount electronic device **32b**.

The mask used at Step **127** is thicker than a total of respective thicknesses of conductor patterns **121** and **131**. This arrangement allows conductor pattern **131** to expose

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from insulating layer **132**, thus ensuring the bonding strength between the side electrode **32c** and the mother board.

In the processes of shown in FIG. **18** for manufacturing surface mount-electronic device shown, conductive paste **112** is baked to provide conductor pattern **121** at Step **102**, and then, conductive paste **112** printed at Step **103** is baked at Step **103** to provide conductor pattern **131**. Step **102** may be eliminated. That is, conductive paste **112** is printed with screen **123** on conductive paste **112** printed with screen **111** at Step **101**. Then, conductive pastes **112** are baked together to provide conductor patterns **121** and **131**, simultaneously.

What is claimed is:

1. An electronic device comprising:

a substrate having an upper surface and a side surface;
a first conductor pattern provided over the upper surface of the substrate, the first conductor pattern having a first portion and a second portion connected with the first portion, the second portion being higher than the first portion, the second portion exposing on a plane flush with the side surface of the substrate; and

a first insulating layer provided on the first conductor pattern and over the upper surface of the substrate, the insulating layer having an upper surface and a side surface on the plane flush with the side surface of the substrate,

wherein the second portion of the first conductor pattern contacts the substrate and the first insulating layer in the plane.

2. The electronic device according to claim **1**, further comprising a second conductor pattern provided between the first insulating layer and the upper surface of the substrate, the second conductor pattern having a third portion and a fourth portion connected with the third portion of the second conductor pattern, the fourth portion exposing at the upper surface of the first insulating layer.

3. The electronic device according to claim **2**, further comprising:

a third conductor pattern provided on the fourth portion of the second conductor pattern and on the upper surface of the first insulating layer; and

a second insulating layer provided on the third conductor pattern and on the upper surface of the first insulating layer, the second insulating layer having an upper surface and a side surface on the plane flushed with the side surface of the substrate.

4. The electronic device according to claim **1**, wherein the second portion of the first conductor pattern exposes at the upper surface of the first insulating layer.

5. An apparatus comprising:

a mother board having an upper surface;
an electronic device including

a substrate having an upper surface and a side surface,
a conductor pattern provided over the upper surface of the substrate, the conductor pattern having a first portion and a second portion connected with the first portion, the second portion being higher than the first portion, the second portion having a first surface exposing on a plane flush with the side surface of the substrate, and

an insulating layer provided on the conductor pattern and over the upper surface of the substrate, the insulating layer having an upper surface and a side surface on the plane flush with the side surface of the substrate, wherein the second portion of the first conductor pattern contacts the substrate and the first insulating layer in the plane; and

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a land provided on the upper surface of the mother board and connected with the second portion of the conductor pattern.

6. The apparatus according to claim 5, wherein the second portion of the conductor pattern further has a second surface exposing at the upper surface of the insulating layer, wherein the land is connected with the second surface of the second portion of the conductor pattern of the electronic device, and

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wherein the mother board is provided over the upper surface of the insulating layer of the electronic device.

7. The apparatus according to claim 6, further comprising an electrically-conductive joining material connecting the land with the second surface of the second portion of the conductor pattern of the electronic device.

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